Poster Sessions

304. PTB Seminar VUV and EUV Metrology

Poster List — **Thursday 19.10.2017, Friday 20.10.2017** — **13:00 - 14:00**

No.	First author	Title	Institute/Company
1	V. Deuter	EUV interference and proximity lithography	FZ Jülich
2	H. Lu	Reflection-mode Coherent Diffraction Imaging using Laboratory Light Sources	RWTH
3	K. Jimenez	Optical And Structural Characterization Of Nb, Zr, Nb/Zr, Zr/Nb Thin Films On Si3N4 Membranes Windows	U Padova
4	N. A. Malik	EUV/FUV polarimetric study of Single layer graphene/SiO2 (285nm)/silicon	U Padova
5	K. Wiese	Determination of optical constants in the VUV by combining reflectometry and ellipsometry	PTB
6	R.W.E. van de Kruijs	In-situ stress and in-vacuo LEIS surface metrology of ultrathin film growth	U Twente
7	L. Bahrenberg	Compositional pellicle characterization by EUV reflectance and transmittance measurements	RWTH
8	D. Wilson	On space charge effects in laboratory based photoemission electron microscopy using compact gas discharge EUV sources	FZ Jülich
9	F. Melsheimer	Study of plasma dynamics and spectral tunability in hollow cathode triggered gas-discharge sources	FZ Jülich
10	S. Glabisch	Spectral characterization of the EUV emission of a gas discharge plasma light source ignited by a high voltage trigger	RWTH
11	N. Böwering	Analysis of improvement potential of electrodeless discharge EUV light source for metrology	U Bielefeld
12	V. Zabrodskii	4H - SiC detectors for VUV spectral range	Ioffe
13	A. Sokolov	An XUV At-Wavelength Metrology facility at BESSY-II for precision diffraction gratings	HZB
14	P. Baumgärtel	RAY-UI: Extensions compared to RAY	HZB
15	F. Siewert	The new BESSY-II Optics Laboratory - a Facility for Measuring ultra-precise X-Ray Optics	HZB
16	M. Bayraktar	Broadband spectrometer development based on high-density free-standing transmissioning gratings	MESA U Twente
		Post-Deadline Posters	